

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re divisional patent application of 09/690,875 filed on October 18, 2000

Cohen et al.

Serial No.: Not Yet Assigned

Group Art Unit: Not Yet Assigned

Filing Date: Concurrently Herewith

Examiner: Unknown

For: DOUBLE-GATE FET WITH PLANARIZED SURFACES AND SELF ALIGNED  
SILICIDES

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**INFORMATION DISCLOSURE STATEMENT**

Sir:

Under the provisions of 37 CFR §1.97 through §1.99 and pursuant to applicant's duty of disclosure under 37 CFR §1.56, applicant respectfully brings the following documents listed on the attached form PTO-1449, to the attention of the Examiner in charge of the above-identified application. All of these references were either cited or submitted in parent Application No. 09/690,875 and thus copies of these references are not provided in accordance with 37 C.F.R. §1.98(d).

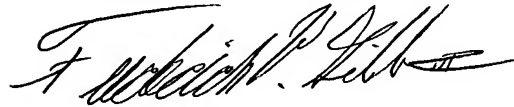
This citation does not constitute an admission that the references are relevant or material to the claims. They are only cited as constituting related art of which the applicant is aware.

It is respectfully requested that the listed references be considered by the Examiner and formally made of record in this application.

YOR920000173US2

Please charge any deficiencies in fees and credit any overpayment of fees to Attorney's  
Deposit Account No. 50-0510.

Respectfully submitted,

A handwritten signature in black ink, appearing to read "Frederick W. Gibb, III", with a stylized flourish at the end.

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# **INFORMATION DISCLOSURE CITATION**

(Use several sheets if necessary)

ATTY DOCKET NO.  
YOR920000173US2

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GROUP  
Unknown

## **U.S. PATENT DOCUMENTS**

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	5,102,819	04/07/1992	Matsushita et al.			
	5,120,666	06/09/1992	Gotou			
	5,166,084	11/24/1992	Pfiester			
	5,273,921	12/28/1993	Neudeck et al.			
	5,371,401	12/06/1994	Kurita			
	5,461,250	10/24/1995	Burghartz et al.			
	5,497,019	05/05/1996	Mayer et al.			
	5,646,058	07/08/1997	Taur et al.			
	5,708,286	01/13/1998	Uesugi et al.			
	5,773,331	06/30/1998	Solomon et al.			
	5,923,963	07/13/1999	Yamanaka			

## **FOREIGN PATENT DOCUMENTS**

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	JP-05-226655	09/1993	Japan				✓

## **OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

		"0.18-um Fully-Depleted Silicon-on-Insulator MOSFET's", Min Cao, Ted Kamins, Paul Vande Voorde, Carlos Diaz, and Wayne Greene, IEEE Electron Device Letters, Vol. 18, No. 6, June 1997, pp.251-252
		"Super Self-Aligned Double-Gate (SSDG) MOSFET's Utilizing Oxidation Rate Difference and Selective Epitaxy", Jong-Ho Lee, Gianni Taraschi, Andy Wei, Tom A. Langdo, Eugene A. Fitzgerald, and Dimitri A. Antoniadis, Microsystems Technology Laboratories, Massachusetts Institute of Technology, Cambridge, MA, IEEE, 1999, pp71-74

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DATE CONSIDERED

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	6,143,582	11/07/2000	Vu et al.			
	6,346,446	02/12/2002	Ritenour			
	6,365,465	04/02/2002	Chan et al.			

**FOREIGN PATENT DOCUMENTS**

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

**OTHER DOCUMENTS** (Including Author, Title, Date, Pertinent Pages, Etc.)

		"Self-Aligned (Top and Bottom) Double-Gate MOSFET with a 25 nm Thick Silicon Channel", Hon-Sum Philip Wong, Kevin K. Chan, and Yuan Taur, IBM Thomas J. Watson Research Center, Yorktown Heights, NY, IEEE 1997, pp. 427-430
		"New Planar Self-Aligned Double-Gate Fully-Depleted P-MOSFET's Using Epitaxial Lateral Overgrowth (ELO) and Selectively Grown Source/Drain (S/D), Taichi Su, John P. Denton, and Gerold W. Neudeck, IEEE School of Electrical and Computer Engineering, Purdue University, West Lafayette, IN, IEEE, 2000, pp. 110-111

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